## **Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

## **Listing of Claims:**

- (currently amended) A fabrication method, comprising the steps of:
  - monitoring the exhaust of a process chamber; and
  - automatically sampling said exhaust when a predetermined event particle excursion occurs.
- (original) The method of Claim 1, wherein said step of monitoring is done using an in-situ particle monitor.
- (original) The method of Claim 1, wherein said step of sampling is done by inserting a collection device into said exhaust.
- 4. (canceled)
- 5. (original) The method of Claim 1, wherein said exhaust is sampled by redirecting said exhaust to a sampling area.
- (original) The method of Claim 1, wherein an electrical control signal of said process chamber is monitored and correlated to said event.
- 7. (currently amended) A fabrication method, comprising the steps of:
  - monitoring at least one signal of a process chamber; and
  - sampling the exhaust from said process chamber when a predetermined event eccurs detecting a given particle flux by an in-situ particle monitor located in said exhaust.
- 8. (original) The method of Claim 7, wherein said signal is an electrical control signal.
- 9. (currently) The method of Claim 7, wherein said predetermined event is the deleting occurs at a variation in said signal.
- 10-13. (canceled)

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- 14. (currently amended) A wafer processing system, comprising:
  - a chamber with an exhaust;
  - a particle monitor located in said exhaust;
  - wherein said particle monitor is connected to cause a particle sampler to gather samples from said exhaust when a predetermined particle flux is detected.
- 15. (original) The system of Claim 14, wherein said sampler gathers samples by being inserted into said exhaust.
- 16. (original) The system of Claim 14, wherein said sampler gathers samples by opening valves so that said exhaust passes to a sampling area.
- 17. (original) The system of Claim 14, wherein said sampler is a membrane filter.
- 18. (canceled)